What is claimed is:

1. A fringe field switching mode liquid crystal display, comprising:

gate lines and data lines aligned on a transparent insulating substrate to vertically cross each other;

common electrode lines aligned horizontally to the gate lines;

a pixel region defined in a space formed by the gate lines and data lines;

a first transparent electrode formed in the pixel region, and divided into at least two regions; and

a second transparent electrode insulated from the first transparent electrode, and divided on the first transparent electrode as many as the first transparent electrode, a data voltage being applied to the second transparent electrode in a first region and to the first transparent electrode in a second region, a sum of the voltages applied to the pixel region having a zero voltage.

2. The device according to claim 1, wherein the first transparent electrode formed in the first region and the second transparent electrode formed in the second region are connected to a common electrode line.

3. The device according to claim 1, wherein the first transparent electrode is formed in a box shape, and the second transparent electrode is formed in a slit shape to apply an electric field to a liquid crystal.

4. The device according to claim 1, wherein the first transparent electrode and the second transparent electrode are used as pixel electrodes.

5. A method for fabricating a fringe field switching mode liquid crystal display having gate lines and data lines aligned on a transparent insulating substrate to vertically cross each other, common electrode lines aligned horizontally to the gate lines, a thin film transistor formed by a source and drain extended from the data line, and the gate line, and a pixel region defined in a space formed by the gate lines and data lines, comprising the steps of:

forming a first transparent electrode in the pixel region to be divided into at least two regions; and

forming a second transparent electrode to be insulated from the first transparent electrode and divided on the first transparent electrode as many as the first transparent

electrode, a data voltage being applied to the second transparent electrode in a first region and to the first transparent electrode in a second region, a sum of the voltages applied to the pixel region having a zero voltage.

6. The method according to claim 5, wherein the step for forming the first transparent electrode forms a first transparent electrode layer in the pixel region defined in a space formed by the gate lines and data lines, and patterns the first transparent electrode layer to form the first transparent electrode divided into at least two regions, the first transparent electrode portions of the first and second regions being isolated.

7. The method according to claim 6, further comprising the steps of:

forming an insulating film over the resultant structure including the first transparent electrode divided into at least two regions, and forming a contact hole on the insulating film to expose the first transparent electrode portion of the second region; and

forming a second transparent electrode layer on the insulating film having the contact hole, and forming a second transparent electrode divided into two regions by

patterning the second transparent electrode layer.

8. The method according to claim 7, wherein the second transparent electrode portion of the first region is connected to a drain of the thin film transistor and the first transparent electrode portion of the second region.

9. The device according to claim 5, wherein the first transparent electrode is formed in a box shape, and the second transparent electrode is formed in a slit shape to apply an electric field to a liquid crystal.